

Sub C7
80. (Amended) A device manufacturing method comprising a step of transferring a device pattern onto a work piece, wherein said transferring step comprises:

illuminating a slit area on a predetermined plane on which a mask is arranged with an illumination beam emerging from a fly-eye type integrator having a plurality of optical elements each of which has a cross sectional shape substantially equal to a shape of said slit area; and

relatively moving said mask and said work piece with respect to said illumination beam, respectively, to perform scanning exposure of said work piece with said illumination beam through said mask.

B3
83. (Amended) A device manufacturing method comprising a step of transferring a device pattern onto a work piece, wherein said transferring step comprises:

illuminating a slit area on a predetermined plane on which a mask is arranged with an illumination beam emerging from an optical integrator, said optical integrator forming a plurality of light source images, in which the number of light source images arranged in a first direction corresponding to a longitudinal direction of said slit area is different from a number of light source images arranged in a second direction crossing said first direction; and

relatively moving said mask and said work piece with respect to said illumination beam, respectively, to perform scanning exposure of said work piece with said illumination beam through said mask.

B4
84. (Amended) A scanning exposure apparatus comprising:

an illumination optical system, an optical axis of said illumination optical system being substantially perpendicular to a slit area on a predetermined plane, said illumination optical system comprising an internal reflection type integrator on said optical axis and an optical device which changes an intensity distribution of an illumination beam on a pupil plane of said illumination optical system, and said illumination optical system illuminating said slit area with said illumination beam; and